

**MSAEI38N10A**  
**MSAFI38N10A**

## Features

- Ultrafast rectifier in parallel with the body diode (MSAE type only)
- Rugged polysilicon gate cell structure
- Increased Unclamped Inductive Switching (UIS) capability
- Hermetically sealed, surface mount power package
- Low package inductance
- Very low thermal resistance
- Uses IRFC250 die
- Reverse polarity available upon request

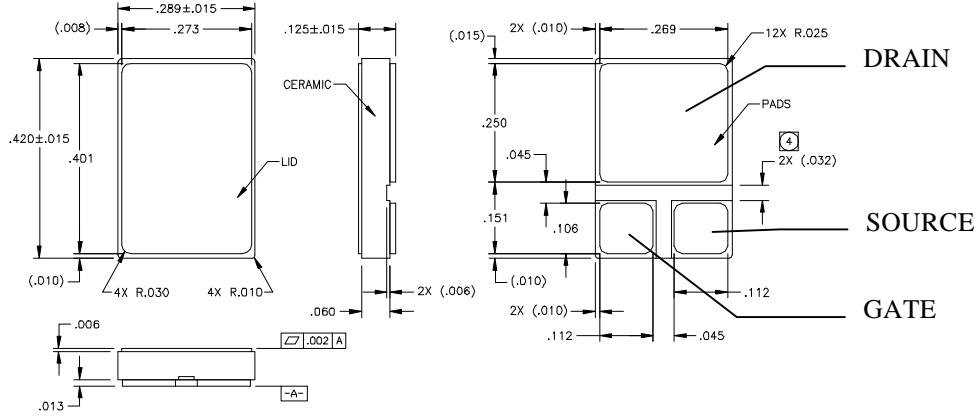
**100 Volts**  
**38 Amps**  
**55 mΩ**

**N-CHANNEL**  
**ENHANCEMENT MODE**  
**POWER MOSFET**

## Maximum Ratings @ 25°C (unless otherwise specified)

DESCRIPTION	SYMBOL	MAX.	UNIT
Drain-to-Source Breakdown Voltage (Gate Shorted to Source) @ T <sub>J</sub> ≥ 25°C	BV <sub>DSS</sub>	100	Volts
Drain-to-Gate Breakdown Voltage @ T <sub>J</sub> ≥ 25°C, R <sub>GS</sub> = 1 MΩ	BV <sub>DGR</sub>	100	Volts
Continuous Gate-to-Source Voltage	V <sub>GS</sub>	+/-20	Volts
Transient Gate-to-Source Voltage	V <sub>GSM</sub>	+/-30	Volts
Continuous Drain Current	I <sub>D25</sub>	38	Amps
T <sub>J</sub> = 25°C	I <sub>D100</sub>	24	
100°C			
Peak Drain Current, pulse width limited by T <sub>Jmax</sub>	I <sub>DM</sub>	150	Amps
Repetitive Avalanche Current	I <sub>AR</sub>	38	Amps
Repetitive Avalanche Energy	E <sub>AR</sub>	15	mJ
Single Pulse Avalanche Energy	E <sub>AS</sub>	150	mJ
Voltage Rate of Change of the Recovery Diode @ I <sub>S</sub> ≤ I <sub>DM</sub> , dI/dt ≤ 100 A/μs, V <sub>DD</sub> ≤ V <sub>DSS</sub> , T <sub>J</sub> ≤ 150°C	dv/dt	5.5	V/ns
Power Dissipation	P <sub>D</sub>	300	Watts
Junction Temperature Range	T <sub>j</sub>	-55 to +150	°C
Storage Temperature Range	T <sub>stg</sub>	-55 to +150	°C
Continuous Source Current (Body Diode)	I <sub>S</sub>	38	Amps
Pulse Source Current (Body Diode)	I <sub>SM</sub>	150	Amps
Thermal Resistance, Junction to Case	θ <sub>JC</sub>	0.4	°C/W

## Mechanical Outline



**MSAEI38N10A**  
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Santa Ana, CA  
**Microsemi**  
Progress Powered by Technology

## Electrical Parameters @ 25°C (unless otherwise specified)

DESCRIPTION	SYMBOL	CONDITIONS	MIN	TYP.	MAX	UNIT
Drain-to-Source Breakdown Voltage (Gate Shorted to Source)	$BV_{DSS}$	$V_{GS} = 0 \text{ V}, I_D = 250 \mu\text{A}$	100			V
Temperature Coefficient of the Drain-to-Source Breakdown Voltage	$\Delta BV_{DSS}/\Delta T_J$			0.13		V/°C
Gate Threshold Voltage	$V_{GS(\text{th})}$	$V_{DS} = V_{GS}, I_D = 1 \text{ mA}$	2.0		4.0	V
Gate-to-Source Leakage Current	$I_{GSS}$	$V_{GS} = \pm 20 \text{ V}_{\text{DC}}, V_{DS} = 0 \text{ V}, T_J = 25^\circ\text{C}$ $T_J = 125^\circ\text{C}$			$\pm 100$ $\pm 200$	nA
Drain-to-Source Leakage Current (Zero Gate Voltage Drain Current)	$I_{DSS}$	$V_{DS} = 0.8 \cdot BV_{DSS} \quad T_J = 25^\circ\text{C}$ $V_{GS} = 0 \text{ V} \quad T_J = 125^\circ\text{C}$			25 250	μA
Static Drain-to-Source On-State Resistance (1)	$R_{DS(on)}$	$V_{GS} = 10 \text{ V}, I_D = 24 \text{ A} \quad T_J = 25^\circ\text{C}$ $I_D = 38 \text{ A} \quad T_J = 25^\circ\text{C}$ $I_D = 24 \text{ A} \quad T_J = 125^\circ\text{C}$			0.055 0.065	Ω
Forward Transconductance (1)	$g_f$	$V_{DS} \geq 15 \text{ V}; I_D = 24 \text{ A}$	9			S
Input Capacitance Output Capacitance Reverse Transfer Capacitance	$C_{iss}$ $C_{oss}$ $C_{rss}$	$V_{GS} = 0 \text{ V}, V_{DS} = 25 \text{ V}, f = 1 \text{ MHz}$	3700 1100 200			pF
Turn-on Delay Time Rise Time Turn-off Delay Time Fall Time	$t_{d(on)}$ $t_r$ $t_{d(off)}$ $t_f$	$V_{GS} = 10 \text{ V}, V_{DS} = 50 \text{ V},$ $I_D = 38 \text{ A}, R_G = 2.35 \Omega$			35 190 170 130	ns
Total Gate Charge Gate-to-Source Charge Gate-to-Drain (Miller) Charge	$Q_{g(on)}$ $Q_{gs}$ $Q_{gd}$	$V_{GS} = 10 \text{ V}, V_{DS} = 50 \text{ V}, I_D = 38 \text{ A}$	50 8 25		125 22 65	nC
Body Diode Forward Voltage (1)	$V_{SD}$	$I_F = I_S, V_{GS} = 0 \text{ V}$ MSAE MSAF			1.2 1.8	V
Reverse Recovery Time (Body Diode)	$t_{rr}$	$I_F = 10 \text{ A},$ $-di/dt = 100 \text{ A}/\mu\text{s},$ MSAE MSAF			50 500	ns
Reverse Recovery Charge	$Q_{rr}$	$I_F = 10 \text{ A},$ $di/dt = 100 \text{ A}/\mu\text{s},$ MSAE MSAF			tbd 2.9	μC

### Notes

- (1) Pulse test,  $t \leq 300 \mu\text{s}$ , duty cycle  $\delta \leq 2\%$
- (2) Microsemi Corp. does not manufacture the nMOSFET die; contact factory for details